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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/618,068	07/14/2003	Ippei Nakamura	Q76351	4323	
23373	7590 07/14/2006		EXAM	INER	
	MION, PLLC	CHOI, LING SIU			
SUITE 800	SYLVANIA AVENUE, N.W	ART UNIT	PAPER NUMBER		
WASHINGTON, DC 20037			1713		
			DATE MAILED: 07/14/2006	6	

Please find below and/or attached an Office communication concerning this application or proceeding.

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•		Application No).	Applicant(s)		
		10/618,068		NAKAMURA ET A	AL.	
	Office Action Summary	Examiner		Art Unit	Γ	
		Ling-Siu Choi		1713		
	he MAILING DATE of this communi		er sheet with the co	rrespondence ac	idress	
Period for R	eply					
WHICHE - Extension after SIX (- If NO peri - Failure to Any reply	TENED STATUTORY PERIOD FO EVER IS LONGER, FROM THE MA is of time may be available under the provisions of (6) MONTHS from the mailing date of this common of for reply is specified above, the maximum star reply within the set or extended period for reply to received by the Office later than three months af itent term adjustment. See 37 CFR 1.704(b).	AILING DATE OF THIS C of 37 CFR 1.136(a). In no event, how unication. Itutory period will apply and will expire will, by statute, cause the application	COMMUNICATION. wever, may a reply be timel e SIX (6) MONTHS from the to become ABANDONED	ly filed e mailing date of this c (35 U.S.C. § 133).		
Status						
1)⊠ Re	sponsive to communication(s) filed	d on 27 April 2006				
·		th on <u>27 April 2000</u> . B)⊠ This action is non-fir	nal			
<u> </u>	nce this application is in condition f	•		ecution as to the	e merits is	
	sed in accordance with the practic	·	•			
Disposition	of Claims					
<u> </u>		!:4:				
·	Claim(s) 1-20 is/are pending in the application.					
	4a) Of the above claim(s) <u>18-20</u> is/are withdrawn from consideration. Claim(s) is/are allowed.					
<u> </u>	aim(s) <u>1-17</u> is/are rejected.					
	aim(s) is/are objected to.					
	aim(s) are subject to restrict	tion and/or election require	ement			
·						
Application	•					
	specification is objected to by the					
	drawing(s) filed on is/are:		•			
	plicant may not request that any objec	= : :	· · · · · · · · · · · · · · · · · · ·			
	placement drawing sheet(s) including					
II)∐ Ine	oath or declaration is objected to	by the Examiner. Note the	e attached Office A	ction or form P1	FO-152.	
Priority unde	er 35 U.S.C. § 119					
12)⊠ Ack	nowledgment is made of a claim f	or foreign priority under 3	5 U.S.C. § 119(a)-(d) or (f).		
a)⊠ A	III b)☐ Some * c)☐ None of:					
1.[2	1. Certified copies of the priority documents have been received.					
	2. Certified copies of the priority documents have been received in Application No					
3.[Copies of the certified copies of	of the priority documents h	nave been received	in this National	Stage	
	application from the Internation	•	· · · ·			
* See	the attached detailed Office action	n for a list of the certified c	opies not received	•		
Attachment(s)		_				
	References Cited (PTO-892) Draftsperson's Patent Drawing Review (PT		Interview Summary (P Paper No(s)/Mail Date	'TO-413)		
	praπsperson's Patent Drawing Review (Pi n Disclosure Statement(s) (PTO-1449 or F		Notice of Informal Pate		O-152)	
	(s)/Mail Date		Other:	•	-	

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DETAILED ACTION

1. This Office Action is in response to the Amendment filed April 27, 2006.

Claims 1-20 are now pending, wherein claims 18-20 have been withdrawn from consideration. The following rejections are based on a new ground. Thus, the Office Action is made as second non-final rejection. In view of the amendment made in claims 18 and 20, claims 18-20 will be rejoined with Group I if the Group I is found allowable.

Claim Analysis

2. Summaries of claims 1-3:

cla	claim A resin composition comprising		esin composition comprising	
3 2		1	Α	an alkali-soluble resin
			В	an infrared absorbing agent
	,	į	С	a thiol compound
			wherein a solubility of the resin composition in an alkaline aqueous solution is changed by exposure with an infrared laser beam	
			whe	erein the thiol compound can tautomerize as followsC(SH)=X- ∏ -C(=S)-X(H)-
			whe	erein X = nitrogen atom or methine group

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3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –
(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth—in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was
- 5. Claims 1, 4-9, and 16-17 are rejected under 35 U.S.C. 102 (b) as anbticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Kenji et al. (JP 54-092526).

Kenji et al. disclose a masking material as ink or coating, comprising a SH group-containing organic sulfur compound with acid stability and heat
resistance, an amine compound, and phenolic and/or rosin type alkali
soluble resin, wherein the -SH group-containing organic sulfur compound is
listed in Table 1 (page 142). However, Kenji et al. are silent on the dependence
of solubility on the exposure with the infraed laser beam. In view of the
substantially identical composition as the present claims, the present composition
would possess such claimed properties. Since the PTO does not have proper
means to conduct experiments, the burden of proof is now shifted to applicants to

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show otherwise. In re Best, 562 F.2d 1252, 195 USPQ 430 (CCPA 1977); In re Fitzgerald, 205 USPQ 594 (CCPA 1980).

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 11-15 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kenji et al. (JP 54-092526) in view of Miura et al. (JP 11-020318 A).

The disclosure of Kenji et al. is adequately disclosed in paragraph 5 and is incorporated herein by reference.

The difference between the present claims and the disclosure of Kenji et al. is the requirement of the specific -SH group-containing organic sulfur compounds used in the composition.

Miura et al. disclose -SH group-containing sulfur compounds represented as formulae (2), (4), and (8) (page 3). Since formula (8) is also disclosed by Kenji et al., -SH group-containing sulfur compounds represented by formula (2) or (4) is equivalent to and exchangeable with the one represented by formula (8). Thus, it would have been obvious to one of ordinary skill in the art at the time the invention was made to use -SH group-containing sulfur compound represented

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by formulae (2) or (4) in the disclosure of Miura because of its equivalence to and exchange with formula (8) and thereby obtain the present invention.

8. Claims 10-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kenji et al. (JP 54-092526) in view of Iguchi et al. (US 4,436,805).

The disclosure of Kenji et al. is adequately disclosed in paragraph 5 and is incorporated herein by reference.

The difference between the present claims and the disclosure of Kenji et al. is the requirement of the specific -SH group-containing organic sulfur compounds used in the composition.

Iguchi et al. disclose -SH group-containing organic sulfur compound represented in the general formula (I), which can be a compound of formula (5) or (8) (col. 3, lines 40 and 60). It is noted that -SH group-containing organic sulfur compound can be represented by the general formula (I). Thus, it would have been obvious to one of ordinary skill in the art at the time the invention was made to use -SH group-containing sulfur compound represented by formulae (5) or (8) in the disclosure of Iguchi and thereby obtain the present invention.

Response to the Applicants' Arguments

9. Applicant's arguments filed on April 27, 2006 have been fully considered but they are not persuasive.

Applicants: "Miura is directed to thermal recording materials, which belong

to a different technical field from the field of masking material for plating as in Kenji. Therefore there is no motivation to even combine the disclosures of Kenji and Miura." And "Since Kenji and Iguchi are directed to different technologies....one would not have been motivated to substitute teachings from Iguchi into Kenji. In particular, Applicants submit that one would not have been motivated to use a compound from a silver complex diffusion transfer process in place of a compound used in a masking material for plating, so one would not have even combined the references."

It is noted that Kenji et al. are silent on the dependence of solubility on the infraed laser-beam exposure. And, Kenji et al. do disclose a masking material comprising substantially identical components. Thus, it is reasonable to believe that Kenji et al. would possess the claimed properties since the claimed properties mainly depends on the combination of the components which form the composition. Since Kenji et al. disclose a thio compound in the general form, which meets the claimed requirement, it implies that any thio compound meeting the general form will satisfy the requirements of the present claims. The species disclosed by Miura or Iguchi do meet the general form of the thio compound. Thus, it is obvious to be used in the disclosure of Kenji et al. and meet the present claims although theses species are disclosed to have other applications.

Conclusion

10. Any inquiry concerning this communication or earlier communications from

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the examiner should be directed to Ling-Siu Choi whose telephone number is 571-272-1098.

If attempt to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Wu, can be reach on 571-272-1114.

LING-SUI CHOI PRIMARY EXAMINER

July 6, 2006